Oxide TFTs
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[AMDp1-15] Effect of Fluorine Doping on Illumination Stability of Solution-Processed IGZO TFTs

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This study investigated the effect of F doping though NBIS comparison between F-doped and conventional IGZO TFTs. The oxygen vacancies in the IGZO layer were reduced and the bandgap of the IGZO was widened by F doping. As a result of this, the illumination stability of F doped-TFTs was improved.